In the Specification:

Substitute the following amended paragraph for the pending paragraph beginning on page 1, line 9:

Attention is directed to commonly owned and assigned copending ~~Application Number, U.S. Serial No. 08/963,360 filed November 3, 1997, entitled "Method and Apparatus for Liquid Developing Material Based Latent Image Development"; and~~ Application Number, U.S. Serial No. 09/182,786 filed November 30, 1998, entitled "Liquid Developers and Processes Thereof"; and Application Number, U.S. Serial NO. 09/385,526 ~~(D/98765)~~ filed August 30, 1999, entitled "Liquid Developers and Processes Thereof."

Substitute the following amended paragraph for the pending paragraph beginning on page 22, line 3:

The present invention in embodiments provides a printing machine which employs the aforementioned liquid developer compositions and development processes. By way of illustration and background of liquid development and the related contact electrostatic printing process, ~~in the aforementioned copending application U.S. Serial No. 08/963,360 (D/97132), the disclosure of which is incorporated by reference herein in its entirety, there is disclosed:~~ <u>a representative imaging system is as follows</u>.

Substitute the following amended paragraph for the pending paragraph beginning on page 22, line 20:

the process nip being defined by a nip entrance and a nip exit, wherein the nip and the nip entrance are operative to apply compressive stress forces on the layer of liquid developing material thereat, and the nip exit is operative to apply tensile stress forces to the layer of liquid developing material for causing imagewise separation of the layer of liquid developing material thereat, for creating a developed image corresponding to the electrostatic latent image; and the layer of liquid developing material being defined by a yield stress threshold in a range sufficient to

allow the layer of liquid developing material to behave substantially as a solid at the nip entrance and in the nip, while allowing the layer of liquid developing material to behave substantially as a liquid along the image/background interfaces at the nip exit. ~~The disclosure of the aforementioned copending application is incorporated herein by reference in its entirety.~~

Substitute the following amended paragraph for the pending paragraph as previously amended on July 23, 2001, beginning on page 26, line 14:

One hundred forty six point two (146.2) grams of NUCREL RX-76®, a copolymer of ethylene and methacrylic acid with a melt index of about 800, available from E.I. DuPont de Nemours & Company, Wilmington, Del., and 405 grams of ISOPAR-M® (Exxon Corporation) were added to a Union Process 1S attritor (Union Process Company, Akron, Ohio) charged with 0.1857 inch (4.76 millimeters) diameter carbon steel balls. The mixture was milled in the attritor, which was heated with running steam through the attritor jacket to about 80°C to 115°C. for 15 minutes. Next, 107.6 grams of the magenta pigment (Sun Rhodamine Y 18:3) available from Sun Chemicals, and 16.2 grams of a reconstitution promoting compound ~~Elvax~~ ELVAX 200W, available from E.I. DuPont de Nemours & Company, as added to the attritor. The resulting mixture was milled in the attritor, which was maintained at 80°C to 115°C for 2 hours with running steam through the attritor jacket. 675 Grams of ISOPAR-M® were added to the attritor at the conclusion of 2 hours, and cooled to 23°C by running water through the attritor jacket, and the contents of the attritor were ground for an additional 4 hours. Additional ISOPAR-M®, about 600 grams, was added and the mixture was separated from the steel balls.

Substitute the following amended paragraph for the pending paragraph as previously amended on July 23, 2001, beginning on page 27, line 1:

The liquid developer solids contain 40 percent by weight of Rhodamine Y magenta pigment; 6% ELVAX 200W reconstitution promoting compound and 54 percent NUCREL RX-76® toner resin. The solids level was 12.873 percent and the ~~Isopar M~~ ISOPAR M level was 87.127 percent of this developer.